## Kenji Nomura

# List of Publications by Year in Descending Order

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96 17,509 47 101 h-index g-index citations papers 19,081 6.4 101 5.1 L-index avg, IF ext. citations ext. papers

#	Paper	IF	Citations
96	Voltage Transfer Characteristics of CMOS-Like Inverters for Ambipolar SnO Thin-Film Transistors.  IEEE Electron Device Letters, <b>2022</b> , 43, 52-55	4.4	2
95	Toward the Development of High-Performance p -Channel Oxide-TFTs and All-Oxide Complementary Circuits <b>2022</b> , 519-538		
94	Defects and Relevant Properties <b>2022</b> , 93-103		
93	Artificial Synapse Based on a 2D-SnO Memtransistor with Dynamically Tunable Analog Switching for Neuromorphic Computing. <i>ACS Applied Materials &amp; Amp; Interfaces</i> , <b>2021</b> ,	9.5	9
92	Atomically Thin Tin Monoxide-Based p-Channel Thin-Film Transistor and a Low-Power Complementary Inverter. ACS Applied Materials & Interfaces, 2021,	9.5	6
91	8-3: Invited Paper: Back-Channel Defect Termination for p-Channel Oxide-TFTs. <i>Digest of Technical Papers SID International Symposium</i> , <b>2021</b> , 52, 85-88	0.5	1
90	Back-Channel Defect Termination by Sulfur for p-Channel CuO Thin-Film Transistors. <i>ACS Applied Materials &amp; Amp; Interfaces</i> , <b>2020</b> , 12, 51581-51588	9.5	15
89	Switching Mechanism behind the Device Operation Mode in SnO-TFT. <i>Advanced Electronic Materials</i> , <b>2020</b> , 6, 2000742	6.4	13
88	Threshold switching of non-stoichiometric CuO nanowire for selector application. <i>Applied Physics Letters</i> , <b>2020</b> , 116, 023503	3.4	9
87	Frequency- and Power-Dependent Photoresponse of a Perovskite Photodetector Down to the Single-Photon Level. <i>Nano Letters</i> , <b>2020</b> , 20, 2144-2151	11.5	15
86	Hydrogen-Defect Termination in SnO for p-Channel TFTs. ACS Applied Electronic Materials, 2020, 2, 116	2 <sub>4</sub> 1168	3 23
85	Resistive switching memory effects in p-type hydrogen-treated CuO nanowire. <i>Applied Physics Letters</i> , <b>2020</b> , 117, 043502	3.4	3
84	P-2: Hydrogenated SnO for p-channel oxide Thin Film Transistor. <i>Digest of Technical Papers SID International Symposium</i> , <b>2020</b> , 51, 1315-1318	0.5	
83	Electronic Defects in Amorphous Oxide Semiconductors: A Review. <i>Physica Status Solidi (A) Applications and Materials Science</i> , <b>2019</b> , 216, 1800372	1.6	103
82	. Journal of Display Technology, <b>2014</b> , 10, 979-983		15
81	Roles of Hydrogen in Amorphous Oxide Semiconductor In-Ga-Zn-O: Comparison of Conventional and Ultra-High-Vacuum Sputtering. <i>ECS Journal of Solid State Science and Technology</i> , <b>2014</b> , 3, Q3085-Q	9090	43
80	Examination of the ambient effects on the stability of amorphous indium-gallium-zinc oxide thin film transistors using a laser-glass-sealing technology. <i>Applied Physics Letters</i> , <b>2014</b> , 105, 133503	3.4	16

### (2011-2013)

79	Surface reactivity and oxygen migration in amorphous indium-gallium-zinc oxide films annealed in humid atmosphere. <i>Applied Physics Letters</i> , <b>2013</b> , 103, 201904	3.4	26
78	P.3: 3-D Stacked Complementary TFT Devices using n-type \(\frac{1}{2}\)GZO and p-type F8T2 TFTs \(\frac{1}{2}\)Operation Confirmation of NOT and NAND Logic Circuits \(\frac{1}{2}\)Digest of Technical Papers SID International Symposium, 2013, 44, 995-998	0.5	1
77	Hydrogen passivation of electron trap in amorphous In-Ga-Zn-O thin-film transistors. <i>Applied Physics Letters</i> , <b>2013</b> , 103, 202114	3.4	92
76	Operation model with carrier-density dependent mobility for amorphous IntaInt thin-film transistors. <i>Thin Solid Films</i> , <b>2012</b> , 520, 3791-3795	2.2	11
75	Effects of low-temperature ozone annealing on operation characteristics of amorphous In La In thin-film transistors. <i>Thin Solid Films</i> , <b>2012</b> , 520, 3787-3790	2.2	30
74	Photovoltaic properties of n-type amorphous IntaInto and p-type single crystal Si heterojunction solar cells: Effects of Ga content. <i>Thin Solid Films</i> , <b>2012</b> , 520, 3808-3812	2.2	18
73	Stability and high-frequency operation of amorphous Inta Into thin-film transistors with various passivation layers. <i>Thin Solid Films</i> , <b>2012</b> , 520, 3778-3782	2.2	69
72	Amorphous Intaint Dual-Gate TFTs: Current Voltage Characteristics and Electrical Stress Instabilities. <i>IEEE Transactions on Electron Devices</i> , <b>2012</b> , 59, 1928-1935	2.9	40
71	Unusually large enhancement of thermopower in an electric field induced two-dimensional electron gas. <i>Advanced Materials</i> , <b>2012</b> , 24, 740-4	24	71
70	Maximum applied voltage detector using amorphous InCaInD thin-film transistor exposed to ozone annealing. <i>Solid-State Electronics</i> , <b>2012</b> , 75, 74-76	1.7	4
69	Light Irradiation History Sensor Using Amorphous In-Ga-Zn-O Thin-Film Transistor Exposed to Ozone Annealing. <i>IEEE Electron Device Letters</i> , <b>2012</b> , 33, 384-386	4.4	6
68	Simple Analytical Model of On Operation of Amorphous In La In Thin-Film Transistors. <i>IEEE Transactions on Electron Devices</i> , <b>2011</b> , 58, 3463-3471	2.9	47
67	Solid-phase epitaxial growth of (111)-oriented Si film on InGaO3(ZnO)5 buffer layer. <i>Journal of Materials Science: Materials in Electronics</i> , <b>2011</b> , 22, 920-923	2.1	
66	Excimer laser crystallization of InGaZnO4 on SiO2 substrate. <i>Journal of Materials Science: Materials in Electronics</i> , <b>2011</b> , 22, 1694-1696	2.1	6
65	Ambipolar oxide thin-film transistor. Advanced Materials, 2011, 23, 3431-4	24	207
64	. IEEE Electron Device Letters, <b>2011</b> , 32, 1695-1697	4.4	69
63	Electronic Structure and Photovoltaic Properties of n-Type Amorphous In-Ga-Zn-O and p-Type Single Crystal Si Heterojunctions. <i>Electrochemical and Solid-State Letters</i> , <b>2011</b> , 14, H346		10
62	Operation Characteristics of Thin-Film Transistors Using Very Thin Amorphous Intaint Channels. <i>Electrochemical and Solid-State Letters</i> , <b>2011</b> , 14, H197		43

61	Large Photoresponse in Amorphous Intaint and Origin of Reversible and Slow Decay. Electrochemical and Solid-State Letters, <b>2010</b> , 13, H324		54
60	Sputtering formation of p-type SnO thin-film transistors on glass toward oxide complimentary circuits. <i>Applied Physics Letters</i> , <b>2010</b> , 97, 072111	3.4	165
59	Three-dimensionally stacked flexible integrated circuit: Amorphous oxide/polymer hybrid complementary inverter using n-type a-InCaZnD and p-type poly-(9,9-dioctylfluorene-co-bithiophene) thin-film transistors. <i>Applied Physics Letters</i> , <b>2010</b> , 96, 263509	3.4	81
58	Intrinsic carrier mobility in amorphous Intalnt thin-film transistors determined by combined field-effect technique. <i>Applied Physics Letters</i> , <b>2010</b> , 96, 262105	3.4	48
57	Present status of amorphous In-Ga-Zn-O thin-film transistors. <i>Science and Technology of Advanced Materials</i> , <b>2010</b> , 11, 044305	7.1	1287
56	Fabrication of Atomically Flat ScAlMgO4 Epitaxial Buffer Layer and Low-Temperature Growth of High-Mobility ZnO Films. <i>Crystal Growth and Design</i> , <b>2010</b> , 10, 1084-1089	3.5	5
55	Origin of definite Hall voltage and positive slope in mobility-donor density relation in disordered oxide semiconductors. <i>Applied Physics Letters</i> , <b>2010</b> , 96, 122103	3.4	121
54	Comprehensive studies on the stabilities of a-In-Ga-Zn-O based thin film transistor by constant current stress. <i>Thin Solid Films</i> , <b>2010</b> , 518, 3012-3016	2.2	45
53	Steady-state photoconductivity of amorphous InCaInD. Thin Solid Films, 2010, 518, 3000-3003	2.2	16
52	Fabrication of GaN epitaxial thin film on InGaZnO4 single-crystalline buffer layer. <i>Thin Solid Films</i> , <b>2010</b> , 518, 2996-2999	2.2	3
51	Device characteristics improvement of a-In@a@n@ TFTs by low-temperature annealing. <i>Thin Solid Films</i> , <b>2010</b> , 518, 3017-3021	2.2	80
50	Field-modulated thermopower in SrTiO3-based field-effect transistors with amorphous 12CaO?7Al2O3 glass gate insulator. <i>Applied Physics Letters</i> , <b>2009</b> , 95, 113505	3.4	48
49	Amorphous Intanto coplanar homojunction thin-film transistor. <i>Applied Physics Letters</i> , <b>2009</b> , 94, 133502	3.4	150
48	Interactive radical dimers in photoconductive organic thin films. <i>Angewandte Chemie - International Edition</i> , <b>2009</b> , 48, 4022-4	16.4	50
47	Large domain growth of GaN epitaxial films on lattice-matched buffer layer ScAlMgO4. <i>Materials Science and Engineering B: Solid-State Materials for Advanced Technology</i> , <b>2009</b> , 161, 66-70	3.1	5
46	Tin monoxide as an s-orbital-based p-type oxide semiconductor: Electronic structures and TFT application. <i>Physica Status Solidi (A) Applications and Materials Science</i> , <b>2009</b> , 206, 2187-2191	1.6	185
45	Effects of post-annealing on (110) Cu2O epitaxial films and origin of low mobility in Cu2O thin-film transistor. <i>Physica Status Solidi (A) Applications and Materials Science</i> , <b>2009</b> , 206, 2192-2197	1.6	59
44	Amorphous Intazn-O thin-film transistor with coplanar homojunction structure. <i>Thin Solid Films</i> , <b>2009</b> , 518, 1309-1313	2.2	50

### (2007-2009)

43	Origins of High Mobility and Low Operation Voltage of Amorphous Oxide TFTs: Electronic Structure, Electron Transport, Defects and Doping. <i>Journal of Display Technology</i> , <b>2009</b> , 5, 273-288		371
42	Electronic Structures Above Mobility Edges in Crystalline and Amorphous In-Ga-Zn-O: Percolation Conduction Examined by Analytical Model. <i>Journal of Display Technology</i> , <b>2009</b> , 5, 462-467		185
41	Anisotropic carrier transport properties in layered cobaltate epitaxial films grown by reactive solid-phase epitaxy. <i>Applied Physics Letters</i> , <b>2009</b> , 94, 152105	3.4	19
40	Trap densities in amorphous-InGaZnO4 thin-film transistors. <i>Applied Physics Letters</i> , <b>2008</b> , 92, 133512	3.4	254
39	Factors controlling electron transport properties in transparent amorphous oxide semiconductors. Journal of Non-Crystalline Solids, <b>2008</b> , 354, 2796-2800	3.9	152
38	p-channel thin-film transistor using p-type oxide semiconductor, SnO. <i>Applied Physics Letters</i> , <b>2008</b> , 93, 032113	3.4	491
37	Modeling of amorphous InGaZnO4 thin film transistors and their subgap density of states. <i>Applied Physics Letters</i> , <b>2008</b> , 92, 133503	3.4	289
36	Epitaxial growth of high mobility Cu2O thin films and application to p-channel thin film transistor. <i>Applied Physics Letters</i> , <b>2008</b> , 93, 202107	3.4	193
35	Photofield-effect in amorphous In-Ga-Zn-O (a-IGZO) thin-film transistors. <i>Journal of Information Display</i> , <b>2008</b> , 9, 21-29	4.1	82
34	Optical and Carrier Transport Properties of Cosputtered ZnIhBnD Films and Their Applications to TFTs. <i>Journal of the Electrochemical Society</i> , <b>2008</b> , 155, H390	3.9	57
33	Subgap states in transparent amorphous oxide semiconductor, InCaInD, observed by bulk sensitive x-ray photoelectron spectroscopy. <i>Applied Physics Letters</i> , <b>2008</b> , 92, 202117	3.4	268
32	Defect passivation and homogenization of amorphous oxide thin-film transistor by wet O2 annealing. <i>Applied Physics Letters</i> , <b>2008</b> , 93, 192107	3.4	243
31	Amorphous oxide channel TFTs. <i>Thin Solid Films</i> , <b>2008</b> , 516, 1516-1522	2.2	155
30	Specific contact resistances between amorphous oxide semiconductor IntaZnD and metallic electrodes. <i>Thin Solid Films</i> , <b>2008</b> , 516, 5899-5902	2.2	171
29	Control of carrier concentration and surface flattening of CuGaO2 epitaxial films for a p-channel transparent transistor. <i>Thin Solid Films</i> , <b>2008</b> , 516, 5790-5794	2.2	32
28	Fabrication of ScAlMgO4 epitaxial thin films using ScGaO3(ZnO)m buffer layers and its application to lattice-matched buffer layer for ZnO epitaxial growth. <i>Thin Solid Films</i> , <b>2008</b> , 516, 5842-5846	2.2	4
27	Giant thermoelectric Seebeck coefficient of a two-dimensional electron gas in SrTiO3. <i>Nature Materials</i> , <b>2007</b> , 6, 129-34	27	794
26	Fast Thin-Film Transistor Circuits Based on Amorphous Oxide Semiconductor. <i>IEEE Electron Device Letters</i> , <b>2007</b> , 28, 273-275	4.4	104

25	Combinatorial approach to thin-film transistors using multicomponent semiconductor channels: An application to amorphous oxide semiconductors in IntaInto system. <i>Applied Physics Letters</i> , <b>2007</b> , 90, 242114	3.4	200
24	Epitaxial film growth, optical, electrical, and magnetic properties of layered oxide In3FeTi2O10. Journal of Applied Physics, 2007, 101, 103714	2.5	6
23	Growth, structure and carrier transport properties of Ga2O3 epitaxial film examined for transparent field-effect transistor. <i>Thin Solid Films</i> , <b>2006</b> , 496, 37-41	2.2	142
22	Epitaxial film growth and superconducting behavior of sodium-cobalt oxyhydrate, NaxCoO2.yH2O (x approximately 0.3, y approximately 1.3). <i>Inorganic Chemistry</i> , <b>2006</b> , 45, 1894-6	5.1	13
21	High-mobility thin-film transistor with amorphous InGaZnO4 channel fabricated by room temperature rf-magnetron sputtering. <i>Applied Physics Letters</i> , <b>2006</b> , 89, 112123	3.4	944
20	Amorphous Oxide Semiconductors for High-Performance Flexible Thin-Film Transistors. <i>Japanese Journal of Applied Physics</i> , <b>2006</b> , 45, 4303-4308	1.4	589
19	Self-Adjusted, Three-Dimensional Lattice-Matched Buffer Layer for Growing ZnO Epitaxial Film: Homologous Series Layered Oxide, InGaO3(ZnO)5. <i>Crystal Growth and Design</i> , <b>2006</b> , 6, 2451-2456	3.5	18
18	Growth and structure of heteroepitaxial thin films of homologous compounds RAO3(MO)m by reactive solid-phase epitaxy: Applicability to a variety of materials and epitaxial template layers. <i>Thin Solid Films</i> , <b>2006</b> , 496, 64-69	2.2	13
17	Device applications of transparent oxide semiconductors: Excitonic blue LED and transparent flexible TFT. <i>Journal of Electroceramics</i> , <b>2006</b> , 17, 267-275	1.5	41
16	Field-Induced Current Modulation in Nanoporous Semiconductor, Electron-Doped 12CaOl Al2O3. <i>Chemistry of Materials</i> , <b>2005</b> , 17, 6311-6316	9.6	39
15	Carrier transport and electronic structure in amorphous oxide semiconductor, a-InGaZnO4. <i>Thin Solid Films</i> , <b>2005</b> , 486, 38-41	2.2	385
14	Growth of epitaxial ZnO thin films on lattice-matched buffer layer: Application of InGaO3(ZnO)6 single-crystalline thin film. <i>Thin Solid Films</i> , <b>2005</b> , 486, 28-32	2.2	13
13	????????? TFT ?????????????????????????	0	
12	Growth mechanism for single-crystalline thin film of InGaO3(ZnO)5 by reactive solid-phase epitaxy. <i>Journal of Applied Physics</i> , <b>2004</b> , 95, 5532-5539	2.5	54
11	Room-temperature fabrication of transparent flexible thin-film transistors using amorphous oxide semiconductors. <i>Nature</i> , <b>2004</b> , 432, 488-92	50.4	5517
10	All oxide transparent MISFET using high-k dielectrics gates. <i>Microelectronic Engineering</i> , <b>2004</b> , 72, 294-7	2 <b>9:8</b> 5	18
9	Carrier transport in transparent oxide semiconductor with intrinsic structural randomness probed using single-crystalline InGaO3(ZnO)5 films. <i>Applied Physics Letters</i> , <b>2004</b> , 85, 1993-1995	3.4	229
8	Electron transport in InGaO3(ZnO)m (m=integer) studied using single-crystalline thin films and transparent MISFETs. <i>Thin Solid Films</i> , <b>2003</b> , 445, 322-326	2.2	11

#### LIST OF PUBLICATIONS

7	Frontier of transparent oxide semiconductors. Solid-State Electronics, 2003, 47, 2261-2267	1.7	123
6	Thin-film transistor fabricated in single-crystalline transparent oxide semiconductor. <i>Science</i> , <b>2003</b> , 300, 1269-72	33.3	1534
5	Novel film growth technique of single crystalline In2O3(ZnO)m (m=integer) homologous compound. <i>Thin Solid Films</i> , <b>2002</b> , 411, 147-151	2.2	35
4	Orientation control of zinc oxide films by pulsed current electrolysis. <i>Journal of Crystal Growth</i> , <b>2002</b> , 235, 224-228	1.6	22
3	Preparation of Zinc Oxide Thin Films by Pulsed Current Electrolysis. <i>Journal of the Electrochemical Society</i> , <b>2002</b> , 149, F76	3.9	20
2	In situObservation of the Crystallization Process of Ferroelectric Thin Films by Raman Microspectroscopy. <i>Japanese Journal of Applied Physics</i> , <b>2000</b> , 39, 5247-5251	1.4	15
1	Recent progress of oxide-TFT-based inverter technology. <i>Journal of Information Display</i> ,1-19	4.1	9